

IN THE CLAIMS:

Please CANCEL claim 24 without prejudice to or disclaimer of the recited subject matter.

Please AMEND claims 19, 20, 22, 25-31 and 37, and ADD new claims 38-41 as follows.

A marked-up copy of the amended claims showing the changes made thereto is attached. Note that all the claims currently pending in this application, including those not currently being amended, have been reproduced below for the Examiner's convenience.

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19. (Amended) An exposure apparatus comprising:

*B*  
an optical system, which directs an exposure beam emitted from a light source onto a substrate, said optical system including a casing and an optical element, said casing having a closed space and said optical element being disposed in the closed space;  
a first supplier, which supplies an inert gas into the closed space;  
a second supplier, which supplies one of oxygen and clean air into the closed space; and  
a discharger, which discharges the gas from the closed space.

*SUB  
C1*  
20. (Amended) An apparatus according to Claim 38, wherein said controller controls said first supplier and said second supplier.

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<sup>2</sup>  
~~21.~~ An apparatus according to Claim ~~20~~<sup>1</sup>, wherein said first supplier comprises a first

<sup>B2</sup> valve, said second supplier comprises a second valve and said controller controls said first valve and said second valve.

<sup>B3</sup> ~~22.~~ (Amended) An apparatus according to Claim ~~20~~<sup>1</sup>, wherein said controller controls a concentration of oxygen in the closed space.

23. An apparatus according to Claim 19, further comprising a mixer which mixes one of oxygen and clean air into the inert gas.

~~24.~~ <sup>4</sup> 25. (Amended) An apparatus according to Claim 19, further comprising a transformer which transforms ozone remaining in the discharged gas into oxygen for reuse thereof.

<sup>sub 2</sup> 26. (Amended) An apparatus according to Claim 38, wherein said controller changes the wavelength of the exposure beam into a wavelength region higher than an oxygen absorptivity when said second supplier supplies the oxygen.

27. (Amended) An apparatus according to Claim 38, wherein said controller changes the wavelength of the exposure beam to a shorter wavelength when said second supplier supplies the oxygen.

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28. (Amended) An apparatus according to Claim 38, further comprising a laser control device which changes the emission laser wavelength region, wherein said controller controls said laser control device.

29. (Amended) An apparatus according to Claim 38, wherein said controller oscillates the wavelength region continuously.  
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30. (Amended) An apparatus according to Claim 38, wherein said controller controls actuation of said light source.

31. (Amended) An apparatus according to Claim 38, wherein said controller inserts a wavelength changing element into a path of the exposure beam.

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32. An apparatus according to Claim 31, wherein said wavelength changing element is a harmonic wave producing element.  
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33. An apparatus according to Claim 19, wherein said optical system comprises one of an illumination optical system and a projection optical system.

34. An apparatus according to Claim 19, wherein said light source comprises one of a light source for producing ultraviolet rays and a light source for producing X-rays.

35. An apparatus according to Claim 19, wherein said light source comprises an ArF excimer laser light source.

36. An apparatus according to Claim 19, wherein said inert gas comprises one of a nitrogen gas, a helium gas, and a neon gas.

37. (Amended) A device manufacturing method comprising the steps of:  
providing an exposure apparatus as recited in Claim 19;  
exposing a substrate by use of the exposure apparatus; and  
developing the exposed substrate.

Please ADD new claims 38-41 as follows:

-- 38. An apparatus according to Claim 19, further comprising a controller for changing a wavelength of the exposure beam between an exposure process for the substrate and a cleaning process for the optical element.

39. An exposure apparatus comprising:  
an optical system, which directs an exposure beam emitted from a light source onto a substrate, said optical system including a casing and an optical element, said casing having a closed space and said optical element being disposed in the closed space;  
a first supplier, which supplies an inert gas into the closed space;